



APR 11 2006
PATENT & TRADEMARK OFFICE
Docket No.: 055071-0328

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of : Customer Number: 20277
Robert SOCHA, et al. : Confirmation Number: 2388
Application No.: 10/756,829 : Group Art Unit: 2825
Filed: January 14, 2004 : Examiner: Suresh Memula

For: METHOD OF OPTICAL PROXIMITY CORRECTION DESIGN FOR CONTACT HOLE MASK

INFORMATION DISCLOSURE STATEMENT

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

Please charge any shortage in fees due in connection with the filing of this paper, including extension of time fees, to Deposit Account 500417 and please credit any excess fees to such deposit account.

Respectfully submitted,

McDERMOTT WILL & EMERY LLP

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Registration No. 36,139

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Date: April 11, 2006



SHEET 1 OF 2

INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)				ATTY. DOCKET NO. 055071-0328	SERIAL NO. 10/756,829	
				APPLICANT Robert John SOCHA, et al.		
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U.S. PATENT DOCUMENTS						
EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code ² (<i>if known</i>)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	
	US	6,413,684 B1	07/02/2002	Stanton		
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FOREIGN PATENT DOCUMENTS						
EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Codes-Number & Kind Codes (<i>if known</i>)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	Translation
						Yes No
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)						
EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.				
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1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.



SHEET 2 OF 2

INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)				ATTY. DOCKET NO. 055071-0328	SERIAL NO. 10/756,829	
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	US					
	US					
	US					
FOREIGN PATENT DOCUMENTS						
EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Code ₃ -Number ₄ -Kind Code ₅ (<i>if known</i>)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	Translation Yes No
		WO 02/03140 A1	01/10/2002	NUMERICAL TECHNOLOGIES, INC.		x
		EP 1 237 046 A2	09/04/2002	ASML MASKTOOLS B.V.		x
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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)						
EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.				
		Christoph DOLAINSKY, et al., "Simulation based method for sidelobe suppression," <i>Optical Microlithography XIII, Proceedings of SPIE</i> , 2000, pp 1156-1162, Vol. 4000				
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		Nicolas Bailey COBB, "Fast Optical and Process Proximity Correction Algorithms for Integrated Circuit Manufacturing," Ph.D. dissertation, Spring 1998, pp 35-72, University of California at Berkeley				
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		J.A. TORRES, et al., "Contrast-Based Assist Feature Optimization," <i>Optical Microlithography XV</i> , 2002, pp 179-187, <i>Proceedings of SPIE</i> , Vol 4691, SPIE				
		Olivier TOUBLAN, et al., "Fully Automatic Side Lobe Detection and Correction Technique for Attenuated Phase Shift Masks," <i>Optical Microlithography XIV</i> , 2001, pp 1541-1547, <i>Proceedings of SPIE</i> , Vol. 4346, SPIE				
		Michael S. YEUNG, "Extension of the Hopkins theory of partially coherent imaging to include thin-film interference effects," <i>Optical/Laser Microlithography VI</i> , 1993, pp 452-463, SPIE, Vol. 1927				
		Douglas VAN DEN BROEKE, et al., "Near 0.3 k ₁ Full Pitch Range Contact Hole Patterning Using Chromeless Phase Lithography (CPL)," <i>Proceedings of the SPIE</i> , September 9, 2003, pp 297-308, Vol. 5256, SPIE				
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